

# A CMOS Pixel Sensor for Precise Measurement on Charge and Track of Cosmic Ray

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on behalf of

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# Outline

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## □ Research Motivation

## □ Architecture of Pixel Sensor Chip

- ❖ Design Goal
- ❖ Process Selection
- ❖ Chip Architecture

## □ R&D of Pixel Sensor Chip

- ❖ Pixel Array and Front-end Circuit
- ❖ Column-end Signal Processing and A/D Conversion
- ❖ Full Function Chip Prototype
- ❖ Chip Readout/Test electronics design

## □ Summary & Future Work

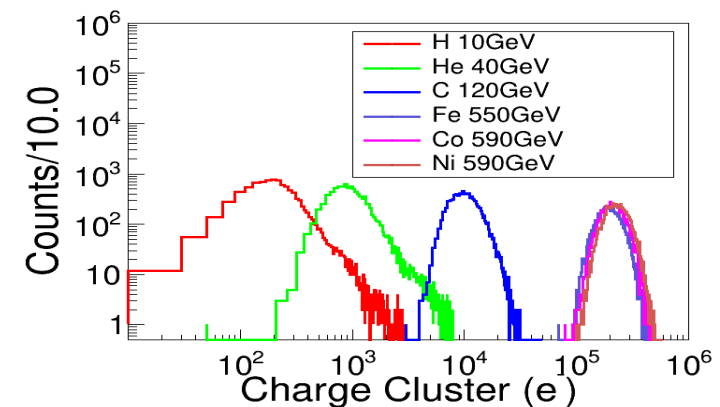
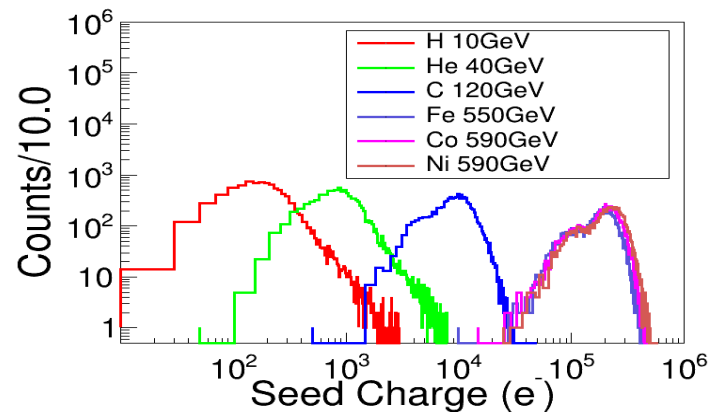
# Motivation

## Measurement of particle charge number practical for silicon pixel sensors

- ❖  $e^-/h^+$  pairs excited proportion to particle ionization energy loss  $dE/dX$
- ❖ ionization energy loss of incident minimum ionization particles proportion to the square of its charge number

$$\text{Bath formula: } -\frac{dE}{dx} = K z^2 \frac{Z}{A} \frac{1}{\beta} \left[ \ln \frac{2m_e c^2 \beta^2 \gamma^2 W_{max}}{I^2} - \beta^2 - \frac{\delta(\beta\gamma)}{2} \right]$$

- Simulation result: Distribution of charge collected by seed pixel and pixel cluster in X-FAB CIS process for different incident particles



# Design Goal

## ❑ Design Goal

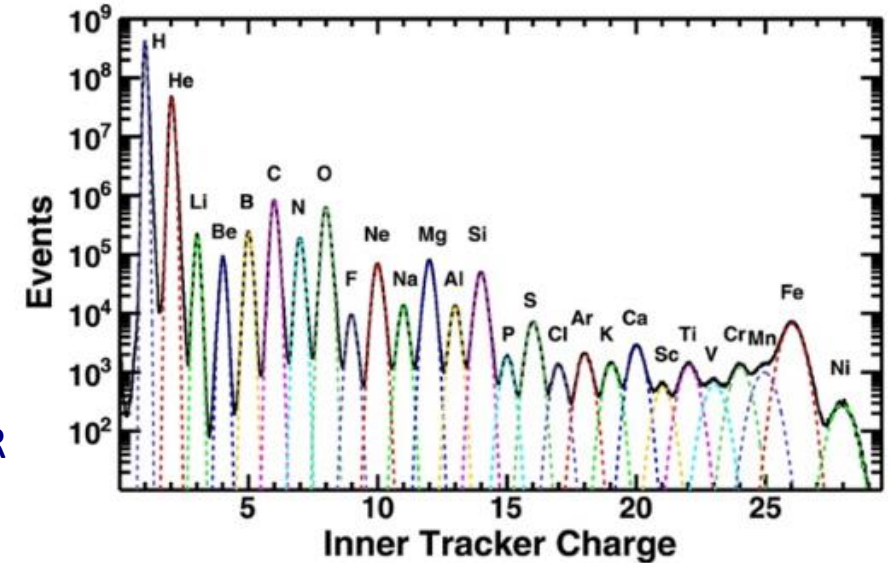
- ❖ distinguish the particle track and nuclear charge number with high precision

## ❑ Physics performance index: same standard with AMS

- ❖ Target **spatial resolution** :  $\sim 10\mu\text{m}$
- ❖ Target **charge resolution** : 1(H)-28(Ni)

## ❑ Sensor performance index

- ❖ Pixel pitch: **50 $\mu\text{m}$**  for  $\sim 10\mu\text{m}$  resolution
- ❖ AD conversion accuracy: LSB 1mV for noise modeling,  $8^+$  bit DR
- ❖ Full scale chip pixel matrix:  $256 \times 256$



Measurement of nuclei charge distribution by AMS inner tracker

# Process selection

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## ❑ Process investigation

### X-fab

- *180nm CIS*
- *EPI Thickness: 5um*
- *EPI resistivity: 8  $\Omega \cdot cm$*

### TowerJazz

- *180nm CIS*
- *EPI Thickness : 18  $\mu m$*
- *EPI resistivity : 1k $\Omega \cdot cm$*

### TSMC

- *180nm CIS*

### Lfoundry

- *180nm CIS*
- *EPI resistivity : >2k $\Omega \cdot cm$*

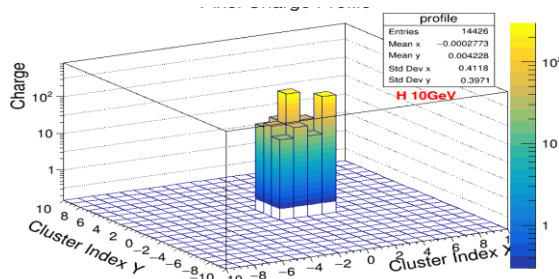
## ❑ Only X-fab provides fabrication service for us

# Process Selection

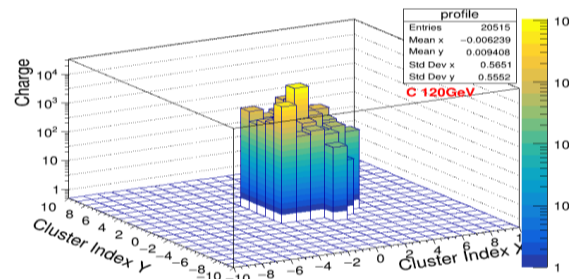
## ❑ Process Performance Evaluation in AllPix<sup>2</sup> + TCAD: charge collect ability

- ❖ Charge collection capacity: low Z nuclei distinguishable, saturate for high Z nuclei (Fe/Co/Ni)
- ❖  $H^+$  excite electron: most in 50+ region
- ❖ Cluster scale: max  $7 \times 7$  for high Z nuclei, DR for most pixels below  $20000e^-$

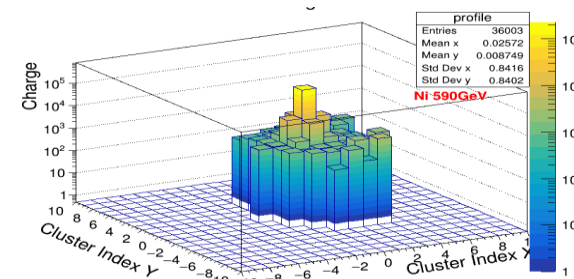
➤ Simulation result: Fire pixel position and charge distribution



❑ Z = 1

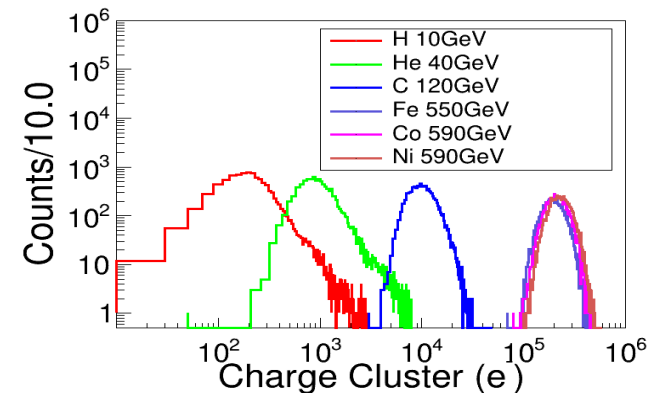
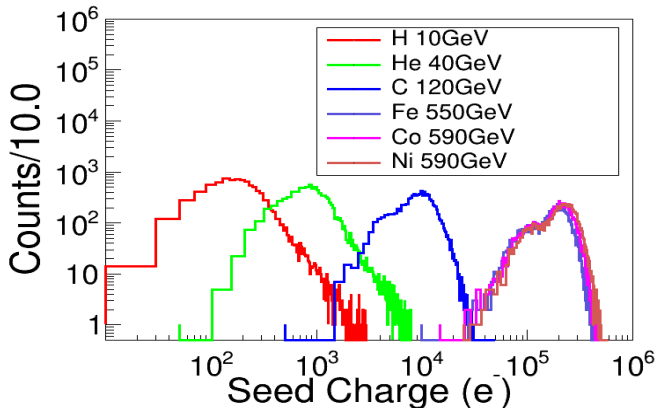


❑ Z = 6



❑ Z = 28

➤ Simulation result: Distribution of charge collected by seed pixel and pixel cluster



# Chip Architecture & Feature—chip overall view

## ❑ X-fab 180nm CIS process

- ❖ 6 metal layers used
- ❖ No deep P-well: PMOS cannot be used in pixel circuit

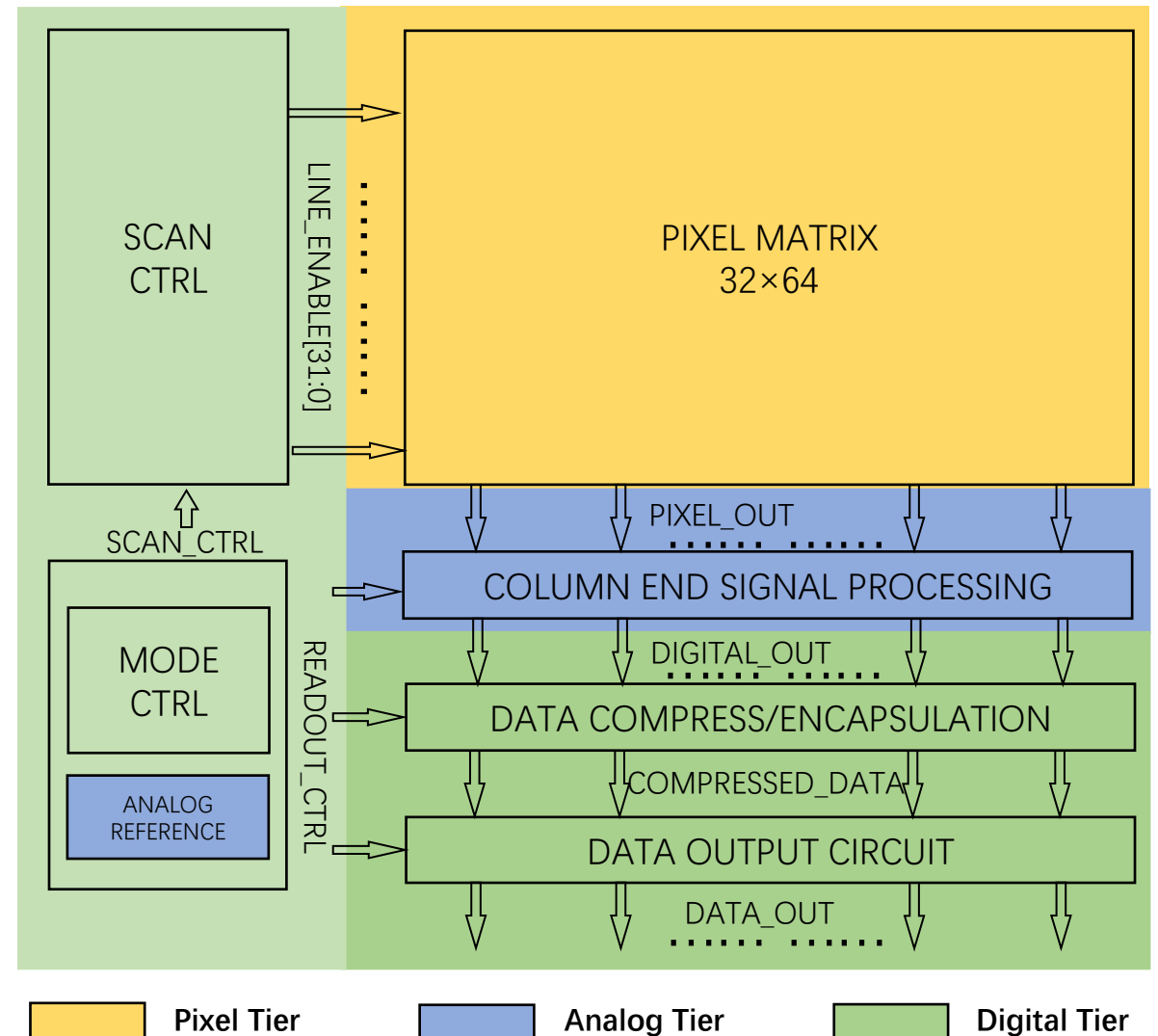
## ❑ Pixel array

- ❖ pixel array: **32 rows × 64 columns** (3 different pixels)
- ❖ Rolling shutter readout mode (600 ns/row)

## ❑ Full functional chip

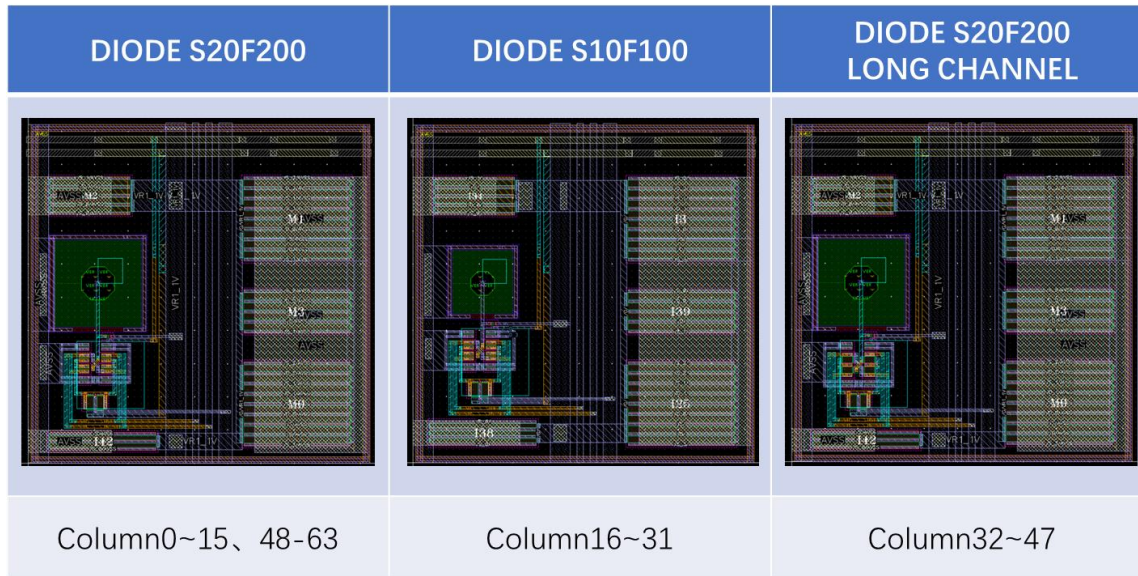
- ❖ Frame rate: 52kHz (19.2us/frame)
- ❖ DR 23000e-, resolution 25e-
- ❖ Row-end **rolling shutter** pixel driving
- ❖ Column-end signal processing (CDS PGA & ADC)
- ❖ On-chip **data compression & encapsulation**
- ❖ Auxiliary modules: Buffers/I2C/BGR .....

## ❑ Full Function Chip Tape-out in Feb 2024





# Pixel Array



## ❑ Octagonal diode:

❖ Diode surface:  $10/20 \mu\text{m}^2$

## ❑ Study RTN (Random Telegraph Noise) performance

❖ Front-end Transistor Size:  $180\text{nm}/500\text{nm} \times 1.5\mu\text{m} \times 2$

## ❑ Diode surface/footprint: 0.1

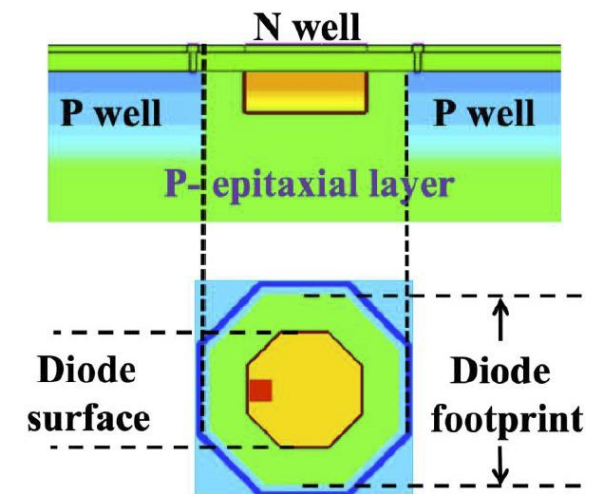
## ❑ Rectangular pixels

❖ Pixel pitch:  $50 \mu\text{m}$

## ❑ 3 different pixels

❖ study charge collection and noise performance

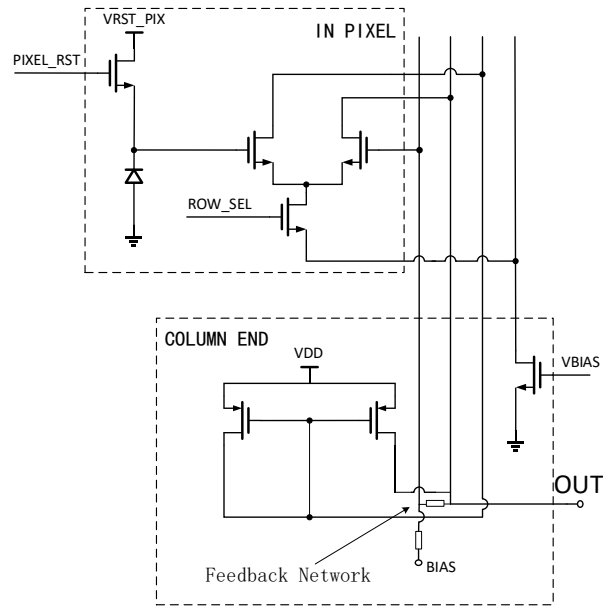
❖ Different diode sizes and transistor sizes



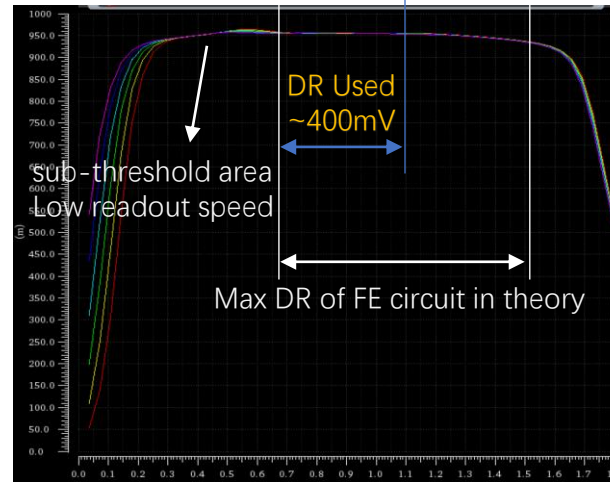


# Front-end Readout Circuit

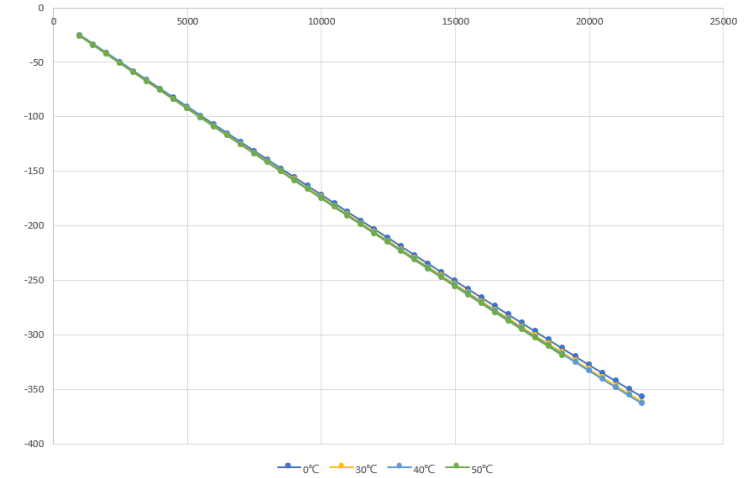
## Front-end circuit



Input Voltage - Small Signal Gain@0°C -50°C

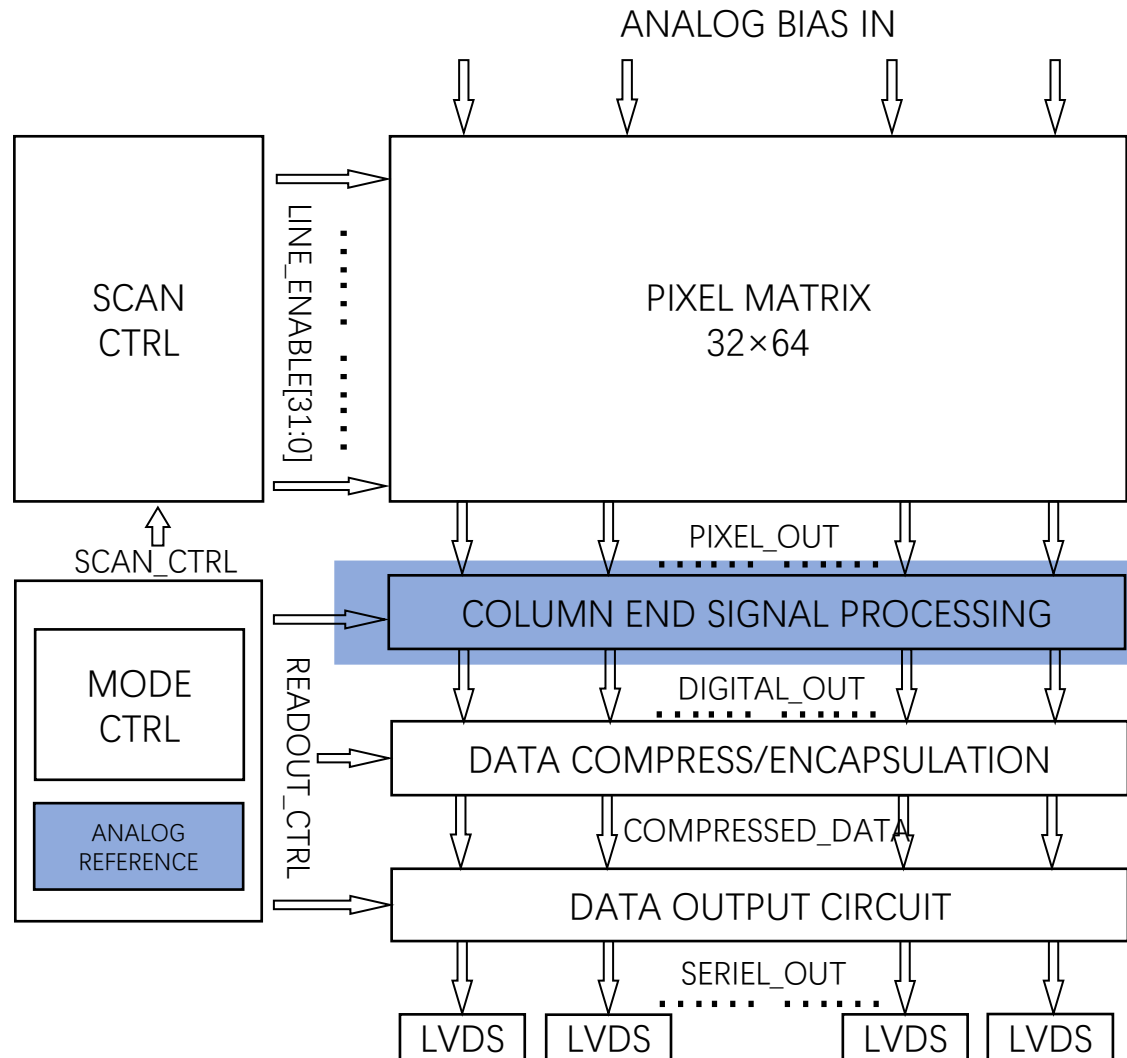


Charge - output voltage@ 0°C -50°C



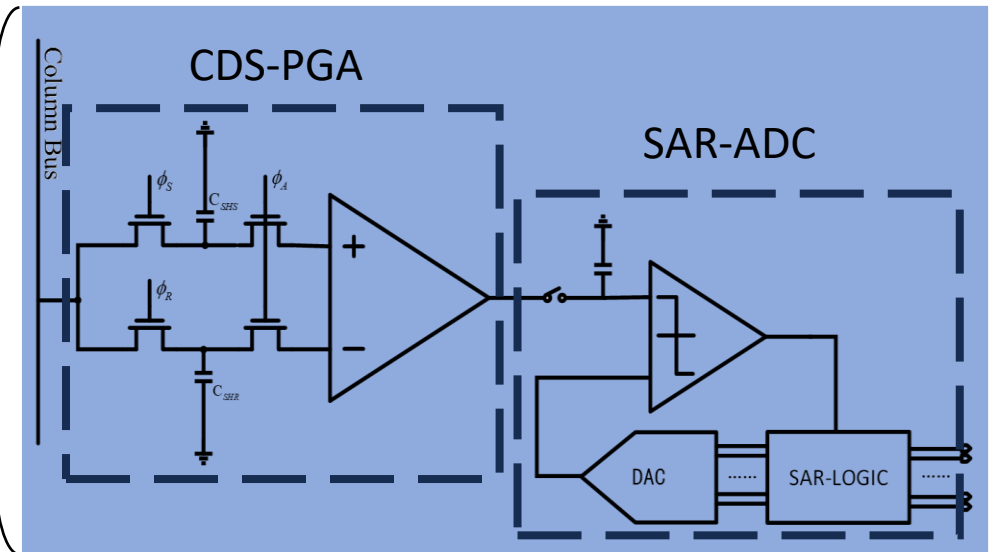
- ❑ Active reset structure
- ❑ Power supply 1.8V
- ❑ All NMOS in pixel
- ❑ Column-level sharing PMOS-type load
- ❑ CDS compatible
- ❑ Close looped 1× (Higher Precision)
- ❑ Better consistency under Different PVT condition(FPN  $10e^{-}$ )
- ❑ Relatively larger DR under low supply power( $23000 e^{-}$ )
- ❑ CVF (Charge-Voltage Factor ):  $16\mu\text{V}/ e^{-}$
- ❑ Better linearity throughout DR

# Column-level Signal Processing

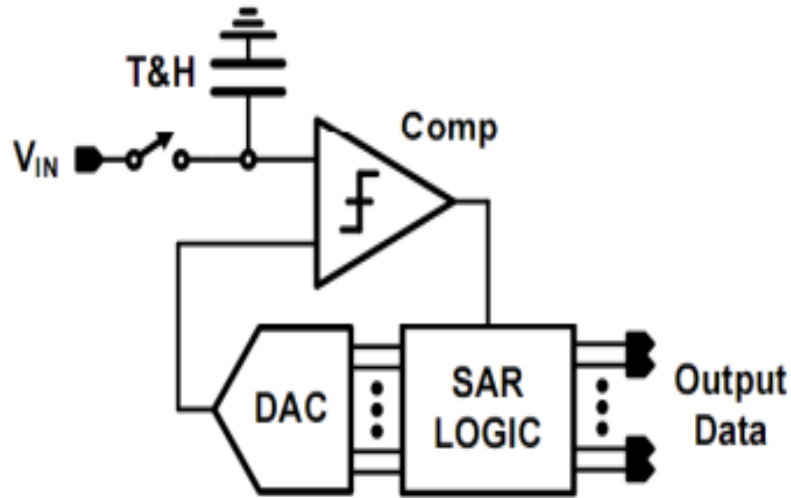


## Circuit function

- ❑ CDS-PGA: Signal Amplify, Reduce Correlated Noise
- ❑ ADC: Convert Analog Signal to Digital region
- ❑ Overall performance: DR 23000e<sup>-</sup> resolution:25 e<sup>-</sup>

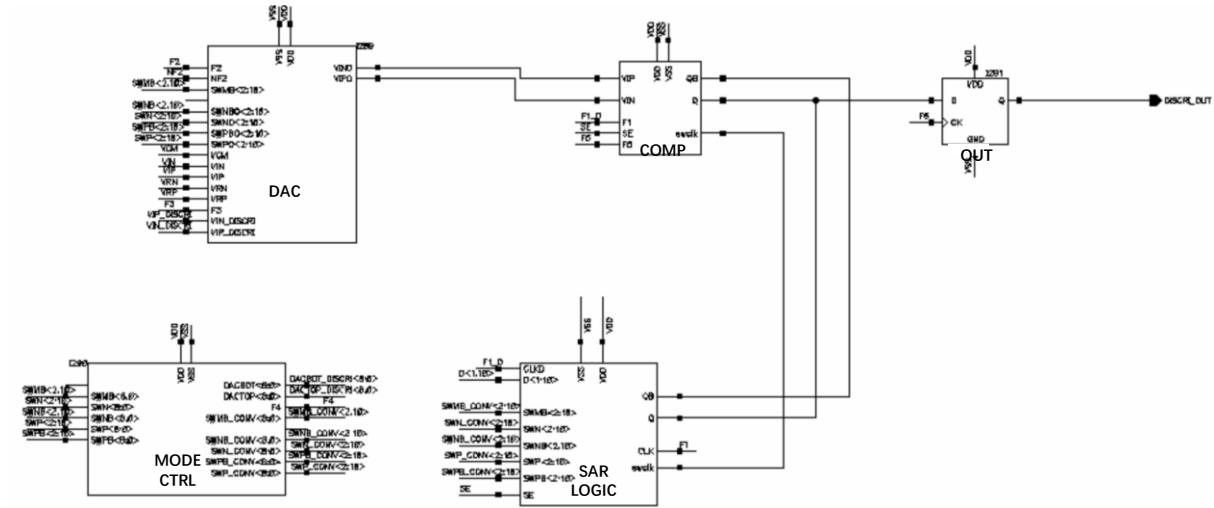


# Column-level Signal Processing —SAR-ADC



## □ SAR-ADC Block Diagram

- ❖ N bit digitization in N clock cycles
- ❖ Op. Amp. free, Low power consumption
- ❖ Circuit size practical for column integration



## □ Implemented SAR-ADC

- ❖ S&H integrated with CDAC
- ❖ Capacitor number minimized using monotonous switching timing & bridge capacitor
- ❖ Asynchronous clock generated for high speed conversion

ADC performance index	ENOB	MAX INL	MAX DNL	Samp. Rate	DR	Area
Value (post-layout sim)	8.9 (10) bit	0.9 LSB	0.6 LSB	10MHz	1.2V $V_{pp}$	50×920 $\mu\text{m}^2$

# Full Function Chip Prototype

## ❑ Chip floorplan

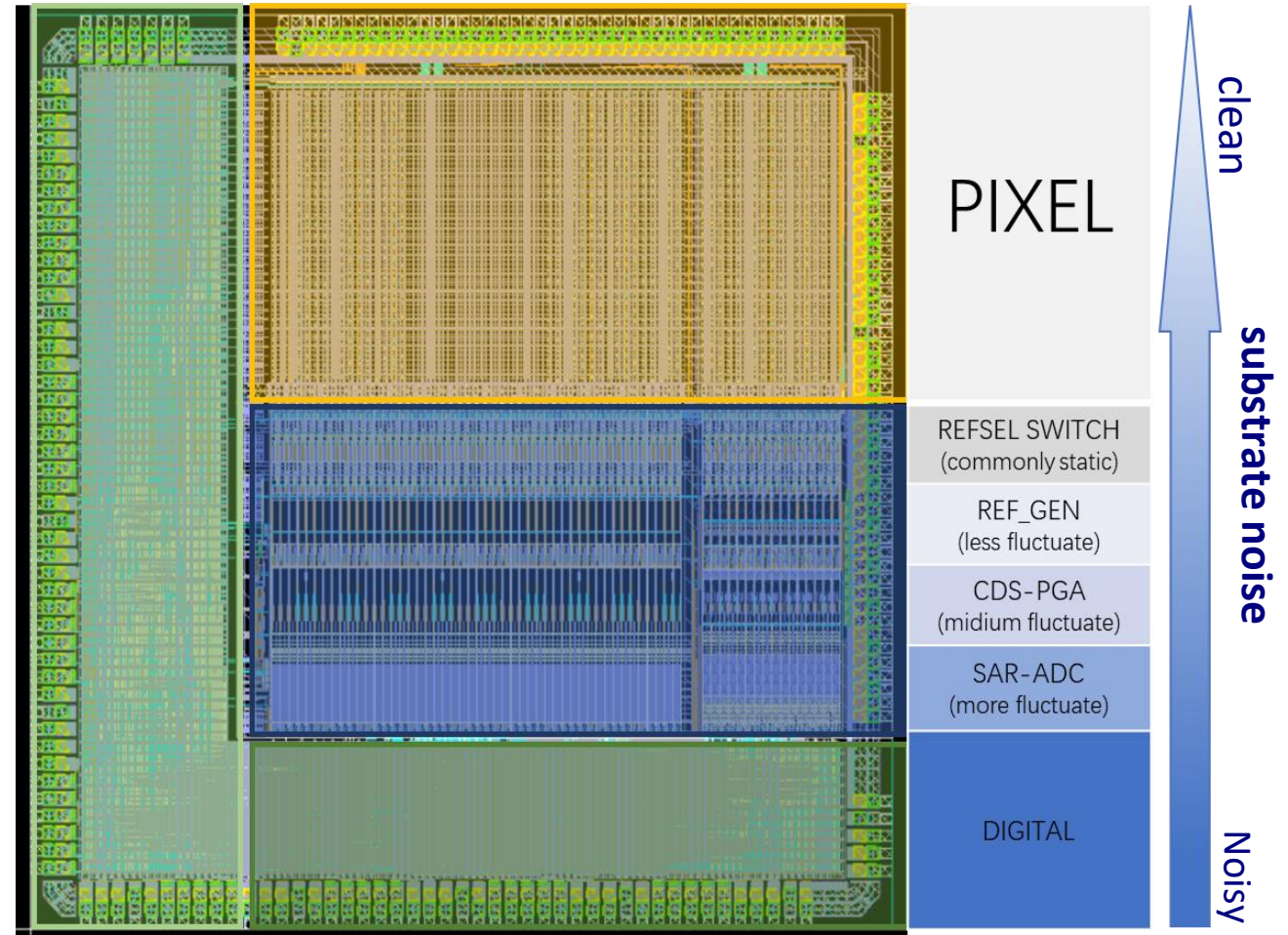
- ❖ Core area:  $5 \times 5 \text{ mm}^2$
- ❖ Pad num. : 193
- ❖ Pixel area:  $4 \times 2 \text{ mm}^2$

## ❑ Layout arrangement

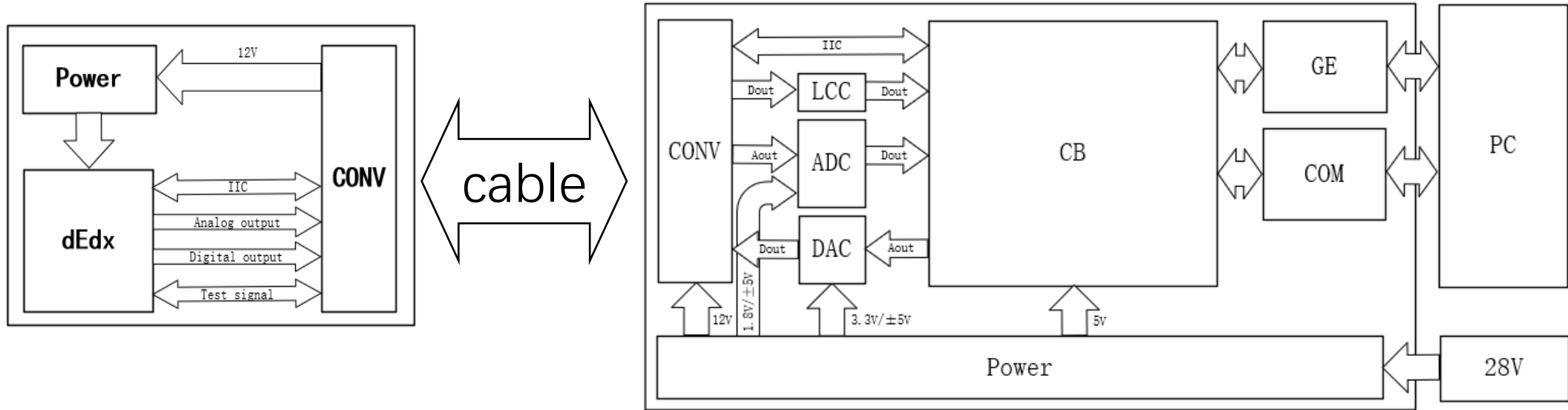
- ❖ arranged in order of substrate noise
- ❖ Clean electrical environment for sensing area

## ❑ Submitted in Feb. 2024

- ❖ Fabrication to be finished in July 2024



# Readout/Test Electronics Design



## ❑ DUT Board

- ❖ Wire bonding
- ❖ Chip power supply, connector

## ❑ Main Board

- ❖ Chip configuration, data acquisition, test signal processing
- ❖ Level convertor, ADC, DAC, FPGA Core Board, Gb Ethernet, COM
- ❖ FPGA Core Board: ZYNQ7020



# Future Work

## ❑ Basic functional testing of chips

- ❖ Probe station, chip function, dEdx function

## ❑ Beam experiment

- ❖  $Z=1\sim 26$
- ❖ The Heavy Ion Research Facility in Lanzhou(HIRFL):  $H_2^+\sim U$ ,  
100~1000MeV/u

## ❑ Chip radiation damage test

- ❖ Space Environment Simulation Research Infrastructure(SESRI):  
哈工大空间环境地面模拟装置质子辐照损失实验
- ❖ Comparison Fe test results of chips before and after irradiation

## ❑ Next full scale chip to be submitted for fabrication after prototype test



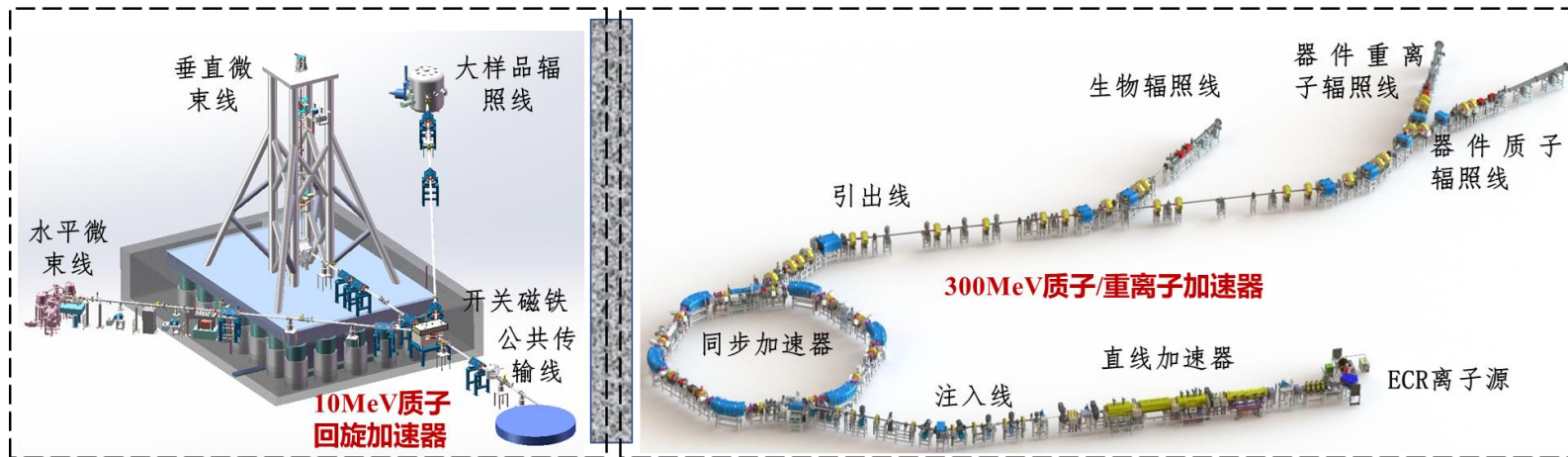
# SESRI: 哈工大十二五国家重大科技基础设施—空间环境地面模拟装置

## □ Ion accelerator system

- ❖ Provide ground simulation radiation sources: P and all heavy ions of He~Bi
- ❖ Low-energy accelerator for 10 MeV **protons**
- ❖ Medium- and high-energy accelerator for 300 MeV proton/heavy ions

## □ Device ion irradiation system

- ❖ High energy proton irradiation terminal: 单粒子效应(SEE)、位移损伤效应(DDD), 总剂量效应(TID)
- ❖ High energy heavy ion irradiation terminal: 重离子辐射效应评测和重离子辐射加固技术验证



低能加速器系统

中高能加速器系统





# SESRI: 哈工大十二五国家重大科技基础设施—空间环境地面模拟装置

□ Part of the 300MeV proton/heavy ion accelerator can accelerate particles and their parameters:

离子	能量 (MeV/u)	LET (MeV·cm <sup>2</sup> /mg)	射程 (μm)
<b>P</b>	100-300	0.0058-0.0029	41.62mm-273.6mm
<b>He</b>	30-80	0.0589-0.0257	4.93mm-28.21mm
<b>C</b>	20-40	0.722-0.4177	813.0-2780
<b>Kr</b>	7-15	35.46-25.64	71.2-167.97
<b>Xe</b>	7-15	64.58-50.36	68.64-148.75
<b>Hf</b>	5-10	85.16-75.78	57.92-106.26
<b>Ta</b>	5-10	86.45-77.2	57.92-105.56
<b>Au</b>	6-8	92.46-89.12	68.48-87.15
<b>Pb</b>	6-7.5	96.44-93.76	68.36-82.46
<b>Bi</b>	6-7.5	97.85-95	68.10-82

# Summary

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- ❑ Proposed Pixel sensor chip can perform particle track and charge distinguish with high precision
- ❑ Charge discrimination of the CMOS pixel sensor is based on ionization energy loss measurement of incident particles
- ❑ The sensor works in rolling shutter mode and will measure ionization excited electrons up to 23000 with ADC in 10-bit accuracy
- ❑ The work is conducted in XFAB 0.18um CIS process and has tape-out in Feb. 2024
- ❑ The sensor prototype is estimated to perform good distinguish performance upon nuclei from H to C and beyond, high Z nuclei distinguish resolution estimated to be low due to saturation

# Thanks

## Acknowledgement

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